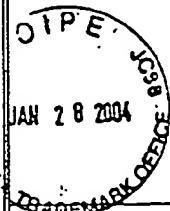


SHEET 1 OF 1

INFORMATION DISCLOSURE
CITATION IN AN
APPLICATION



(PTO-1449)

ATTY. DOCKET NO.
49959-220SERIAL NO.
09/986,137APPLICANT
Gilad ALMOGY, et al.FILING DATE
November 07, 2001GROUP
2881

U.S. PATENT DOCUMENTS

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		EP 1138254 A1	10/04/01	Europe			

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

EXAMINER'S INITIALS	CITE NO.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	
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EXAMINER

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11-17-04

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SHEET 1 OF 1

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				APPLICANT Gilad ALMOGY, et al.		
				FILING DATE November 07, 2001	GROUP 3662	
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		2000068374	03/03/00	Japan		X Abstract
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			APPLICANT Gilad ALMOGY, et al.				
			FILING DATE November 07, 2001	GROUP			
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